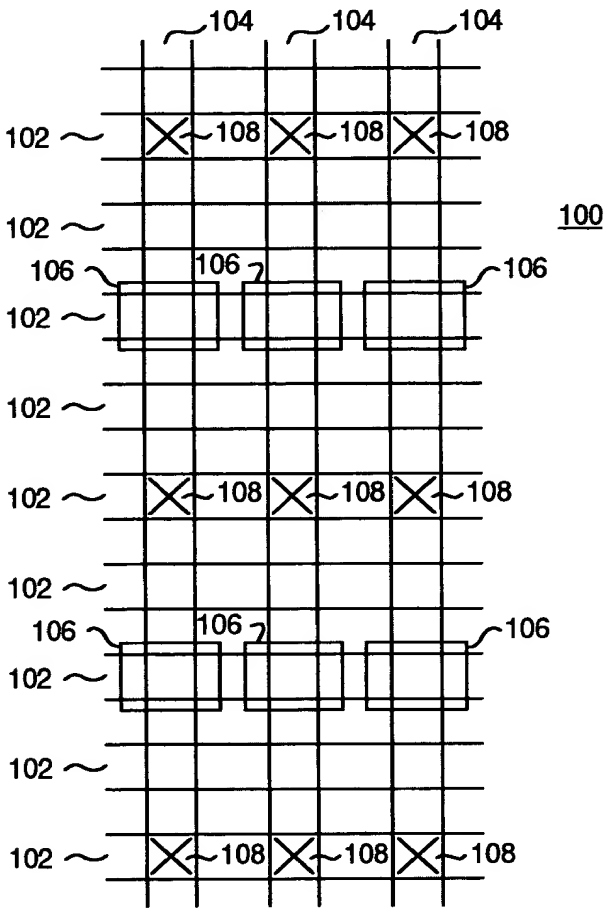

FIG. 1

PRIOR ART

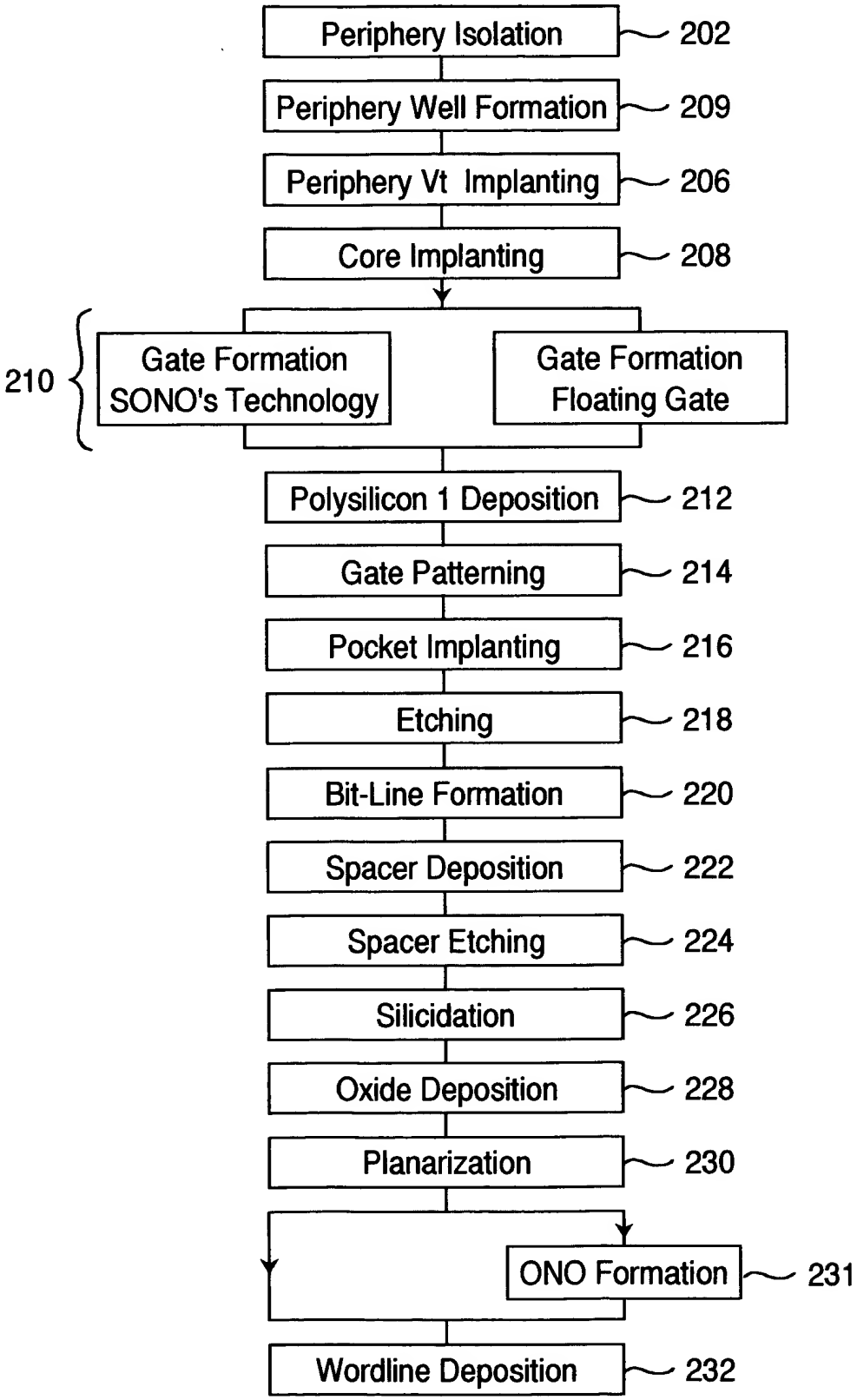
Periphery Isolation
202
Periphery Well Formation
209
Periphery Vt Implanting
206
Core Implanting
208
210
Gate Formation SONO's Technology
Gate Formation Floating Gate
Polysilicon 1 Deposition
212
Gate Patterning
214
Pocket Implanting
216
Etching
218
Bit-Line Formation
220
Spacer Deposition
222
Spacer Etching
224
Silicidation
226
Oxide Deposition
228
Planarization
230
ONO Formation
231
Wordline Deposition
232

FIG. 2

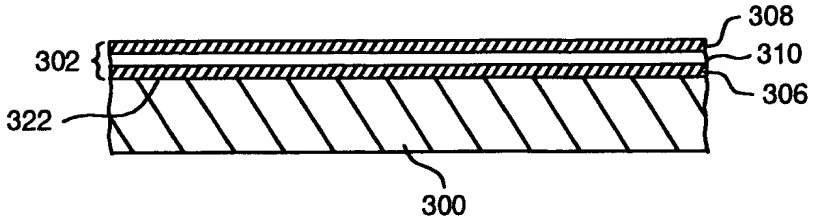

FIG. 3

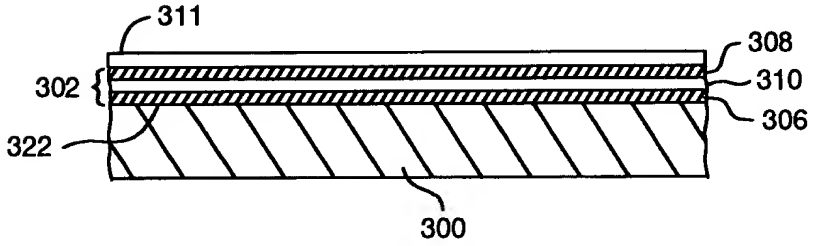

FIG. 4

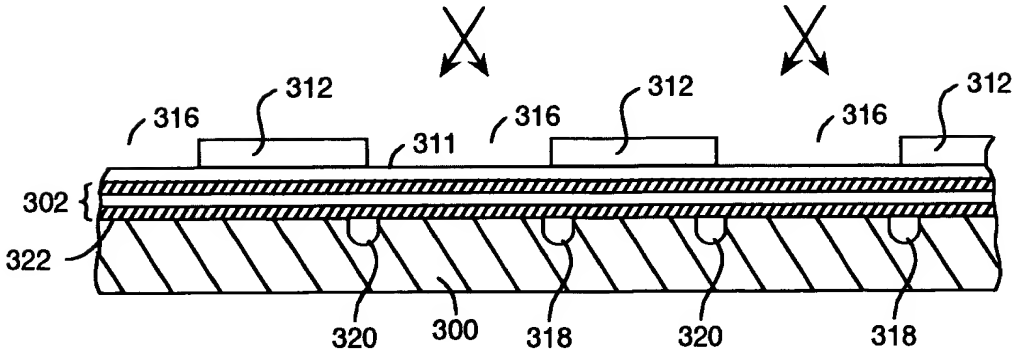

FIG. 5

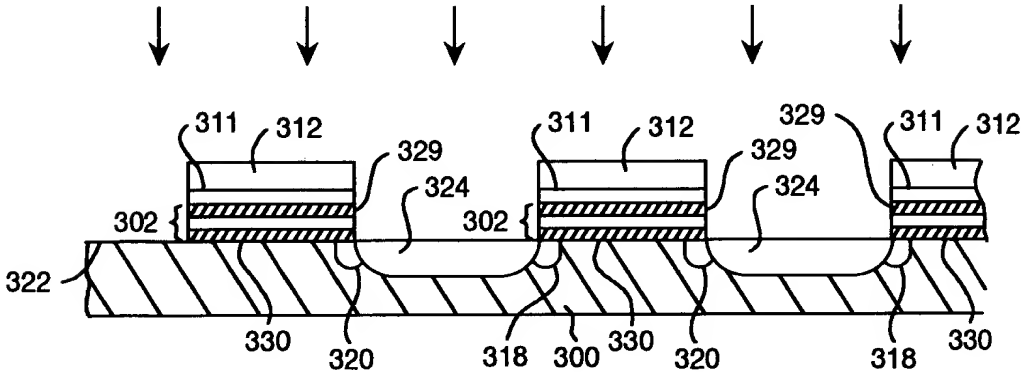

FIG. 6

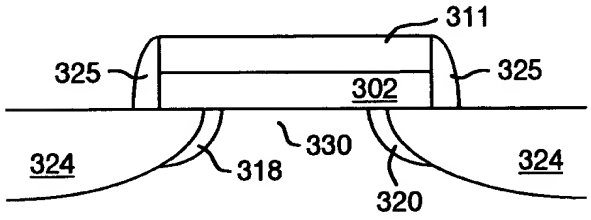

FIG. 7

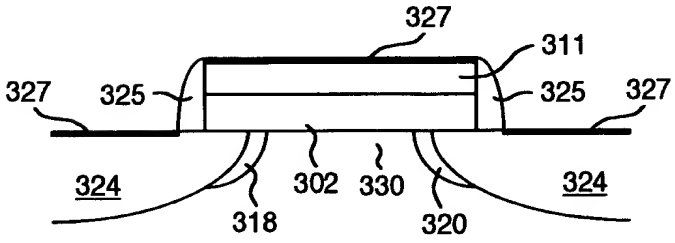

FIG. 8

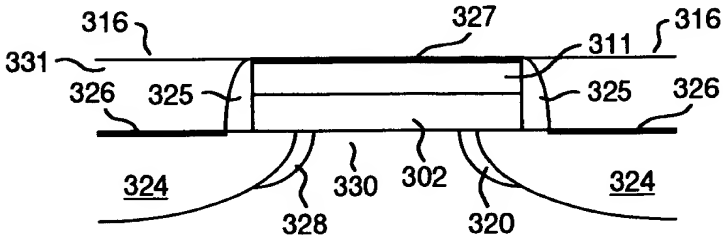

FIG. 9

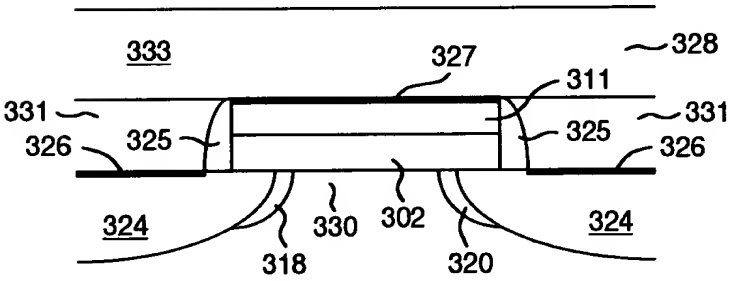

FIG. 10

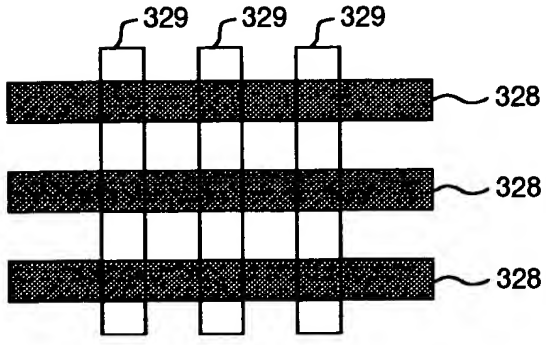

FIG. 11